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MAY 30 2001
TECHNOLOGY CENTER 2800

Please amend the claims as follows.

1. (Amended) A method of manufacturing an active matrix display device wherein said display device has a first substrate provided with a plurality of pixel electrodes and switching thin film transistors for switching said pixel electrodes, and a first electrode comprising a transparent conductive oxide, the method comprising the steps of:

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forming a semiconductor film over a glass substrate;

crystallizing said semiconductor film;

patterning the crystallized semiconductor film into a plurality of semiconductor islands;

forming a plurality of thin film transistors using said semiconductor islands;

forming a driver circuit with said plurality of thin film transistors;

forming a passivation film over said driver circuit;

forming a second electrode comprising a transparent conductive oxide over said passivation film, said second electrode electrically connected to said driver circuit through a contact hole of said passivation film;


attaching said glass substrate provided with said driver circuit to said first substrate so that said second electrode is electrically connected to said first electrode.

2. (Amended) A method of manufacturing a display device comprising:

preparing at least one display substrate provided with first electrodes comprising a transparent conductive oxide;

forming a semiconductor film over a glass substrate;

crystallizing said semiconductor film formed over said glass substrate;

 patterning the crystallized semiconductor film into a plurality of semiconductor islands;

forming a plurality of thin-film transistors with said semiconductor islands for constituting a plurality of driver circuits;

forming a passivation film over said plurality of thin film transistors;

forming second electrodes comprising a transparent conductive oxide over said passivation film, said second electrodes electrically connected to said driver circuits through contact holes of said passivation film;

dividing said glass substrate to obtain at least one divided glass substrate wherein said divided glass substrate carries at least one of said driver circuits and at least one of said second electrodes thereon; and

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met,
attaching said divided glass substrate to a display
substrate so that said at least one of the second electrodes is
electrically connected to said first electrodes.

6. (Amended) A method of manufacturing a display device
comprising:

preparing at least one display substrate provided with
first electrodes wherein said display substrate comprises a
plastic;

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forming a semiconductor film over a glass substrate;
crystallizing said semiconductor film formed over said
display substrate;

patterning the crystallized semiconductor film into a
plurality of semiconductor islands;

forming a plurality of thin film transistors with said
semiconductor islands as an active layer thereof for
constituting a plurality of driver circuits;

forming a passivation film over said plurality of thin film
transistors;

forming second electrodes over said passivation film, said
second electrodes electrically connected to said driver circuits
through contact holes of said passivation film;

dividing said glass substrate to obtain at least one
divided glass substrate wherein said divided glass substrate

carries at least one of said driver circuits thereon and at least one of said second electrodes; and

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ad. attaching said divided glass substrate to a display substrate so that said at least one of the second electrodes is electrically connected to said first electrodes,

wherein both of said first and second electrodes comprise a transparent conductive oxide.

9. (Amended) A method of manufacturing an active matrix type display device comprising:

B3 preparing at least one display substrate provided with a plurality of pixel electrodes and switching thin film transistors for switching said pixel electrodes and first electrodes for supplying signals to said switching thin film transistors;

forming a semiconductor film over a glass substrate;

crystallizing said semiconductor film;

patterning the crystallized semiconductor film into a plurality of semiconductor islands;

forming a plurality of thin film transistors with said semiconductor islands as an active layer thereof for constituting a plurality of driver circuits;

forming a passivation film over said plurality of thin film transistors;

forming second electrodes over said passivation film, said second electrodes electrically connected to said driver circuits through contact holes of said passivation film;

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incl.
dividing said glass substrate to obtain at least one divided glass substrate wherein said divided glass substrate carries at least one of said driver circuits thereon and at least one of said second electrodes; and

attaching said divided glass substrate to a display substrate so that said at least one of the second electrodes is electrically connected to at least one of said first electrodes,

wherein both of said first and second electrodes comprise a transparent conductive oxide.

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12. (Amended) A method of manufacturing an active matrix type display device comprising:

preparing at least one display substrate provided with a plurality of pixel electrodes and switching thin film transistors for switching said pixel electrodes and first electrodes for supplying signals to said thin film transistors;

forming a semiconductor film over a glass substrate;

crystallizing said semiconductor film wherein the crystallization is promoted by adding a catalyst to said semiconductor film;

patterning the crystallized semiconductor film into a plurality of semiconductor islands;

forming a plurality of thin film transistors with said semiconductor islands as an active layer thereof for constituting a plurality of driver circuits;

forming a passivation film over said plurality of thin film transistors;

forming second electrodes over said passivation film, said second electrodes electrically connected to said driver circuits through contact holes of said passivation film;

dividing said glass substrate to obtain at least one divided glass substrate wherein said divided glass substrate carries at least one of said driver circuits thereon and at least one of said second electrodes; and

attaching said divided glass substrate to a display substrate so that said at least one of the second electrodes is electrically connected to said first electrodes,

wherein both of said first and second electrodes comprise a transparent conductive oxide.

16. (Amended) A method of manufacturing a display device comprising:

preparing at least one display substrate provided with a plurality of first electrodes comprising a transparent oxide;

forming a semiconductor film over a glass substrate;
crystallizing said semiconductor film;
patterning the crystallized semiconductor film into a
plurality of semiconductor islands;

forming a plurality of thin film transistors with said
semiconductor islands as an active layer thereof for
constituting a plurality of driver circuits;

forming a passivation film over the plurality of thin film
transistors;

forming transparent electrodes over said passivation film
wherein said transparent electrodes comprise a transparent
conductive oxide;

forming metal bumps on said transparent electrodes;

dividing said glass substrate to obtain at least one
divided glass substrate wherein said divided glass substrate
carries at least one of said driver circuits thereon; and

attaching said divided glass substrate to a display
substrate so that said driver circuit is electrically connected
to said first electrodes through said transparent electrodes and
said metal bumps.